

SUBSTRATE SUPPORT AND PLASMA PROCESSING APPARATUS

ABSTRACT

5 A disclosed substrate support includes a base, an electrostatic
chuck, a sleeve, a first member, and a second member. The electrostatic
chuck is provided on the base, has a first surface including a substrate
supporting surface and a second surface, and provides a first through
10 hole penetrating from the first surface to the second surface. The sleeve
is fixed within the base and defines a second through hole that is aligned
with and communicates with the first through hole. The sleeve includes
a fixing portion that partially defines the inner surface of the sleeve. The
first member is disposed within the first through hole. The second
15 member has a columnar shape, is disposed at least within the second
through hole, and supports the first member. The second member
includes a fixed portion that is fixed by the fixing portion. In a lateral
direction orthogonal to the central axes of both the sleeve and the second
member, a width of the fixing portion is smaller than a width of the fixed
portion.

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[FIG. 3]